Apogee[™] 450 Spin Coater



With DataStream™ Technology

The Cee® Apogee™ precision spin coater delivers track-quality performance with revolutionary interface capabilities and the utmost in chemical compatibility in an efficient, space-saving design. The heavy-duty-drive spin coater combines extremely accurate spin speed control and a high torque drive for aggressive acceleration. Designed for 300-mm and larger wafers and LCD squares up to 14" × 14".

Serving the Semiconductor Industry Since 1987

BENEFITS

- · Compact design for minimized footprint
- Full-color, 7-inch touch screen display
- Drive system (indirect) with highest horsepower in its class
- Enhanced lid-lift assist feature (gas spring opens ≥ 45°)
- Durable benchtop design that is also available in a flange/ deck mountable configuration
- DataStream[™] technology
- Optional X-PRO workstation integrates stand-alone cabinet with an upper exhaust enclosure for process fume control.

BOWL DESIGN

- High-density polyethylene (HDPE) spin bowl
- Versatile lid design allows process flexibility and repeatability
- Optional nitrogen purge for an inert spin environment
- Integrated drain and exhaust ports

PROGRAMMABILITY

- · Touch screen interface and display
- Full-color alphanumeric-capable graphical user interface (GUI)
- A virtually unlimited number of user-defined recipe program steps
- 0.1-second resolution for step times (9,999.9 seconds maximum step time)
- Spin speed: 6,000 rpm
- Spin speed acceleration:
 - 0 to 30,000 rpm/s unloaded
 - 0 to 23,000 rpm/s with a 300-mm substrate
 - 0 to 3,000 rpm/s with a 350mm x 6mm round recessed spin chuck
 - 0 to 400 rpm/s with a 14" \times 14" \times 1.1 mm photomask in a recessed chuck
- Connectivity: USB/Ethernet port for communications for uploading/downloading process parameters with DataStream™ technology
- Simultaneous, automated, multi- dispense capability



PRECISION

- Spin speed repeatability: < 0.2 rpm
- Spin speed resolution: < 0.2 rpm
- \bullet Substrate sizes: < 1 cm to 450 mm round; 14" x 14" square

RELIABILITY

- Indirect drive system protects the spin motor from contact with process chemicals and solvents
- Vacuum and lid interlock
- · Industry-leading reliability and uptime
- 1-year full warranty on parts and labor
- Free remote technical support (phone, email) for the life of the product
- Application process assistance for life of the product

UTILITIES

• Voltage ranges: 208-240 VAC, Single Phase, 50/60 Hz

• Power requirements: 1440 watts (6A)

• Drain port: 3/4" OD

Exhaust port: 1.5" OD, 20 to 50 cfm at 0.2" water (0.6-1.4 cubic meter/min)

• Vacuum: > 20" Hg (< 33 kPa abs)

• Nitrogen or CDA (for automated dispense): 70 psi (482 kPa)

DIMENSIONS

• 27–5/8" (70.2cm) W \times 30–3/4" (78.2cm) D \times 15–1/2" (39.4 cm) H*

Machine weight: 115 lb (52.2 kg)Shipping weight: 250 lb (113.4 kg)

*H is with lid closed. With lid open H is 30-1/4" (76.9cm)

DATASTREAM™ TECHNOLOGY: CONNECTING THE SEMICONDUCTOR INDUSTRY

DataStream[™] technology gives you access to all of your connected Apogee[™] manufacturing equipment in one place to track, access, and modify your systems via a web browser. This technology will give manufacturers the ability to process and visualize data in real time and search and export that data into a number of different formats.

Real-Time Process Information

- Constant feedback of process information for monitoring critical process parameters
- Streamlined interface between different tool types
- Visual cues on process status & health

Advanced Recipe Creation

- Seamless switching between basic and advanced recipe creation methods
- Plain-English recipe translation
- Pre-defined process commands
- Unlimited process steps
- · Unlimited recipe storage

Environmental Monitoring

- Monitoring of temperature & humidity allows for stricter control of critical processes
- Set preconditions and tolerances for monitored parameters
- On-screen, colored visual cues for deviation from controlled specs

Data Logging & Export

- Export data logs into commonly readable formats for further analysis and process troubleshooting
- Increase process efficiency
- Identify process control deviations
- Analyze multiple processes for best known method (BKM) development

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